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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Yasuo MATSUKI, et al.

SERIAL NO.: NEW U.S. PCT APPLICATION

FILED: HERewith

INTERNATIONAL APPLICATION NO.: PCT/JP04/15101

INTERNATIONAL FILING DATE: October 6, 2004

FOR: COMPOSITION FOR FORMING SILICON-COBALT FILM, SILICON-COBALT FILM
AND METHOD FOR FORMING SAME**REQUEST FOR PRIORITY UNDER 35 U.S.C. 119
AND THE INTERNATIONAL CONVENTION**Commissioner for Patents
Alexandria, Virginia 22313

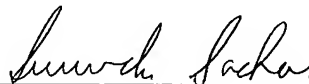
Sir:

In the matter of the above-identified application for patent, notice is hereby given that the applicant claims as priority:

COUNTRY
Japan**APPLICATION NO**
2003-356158**DAY/MONTH/YEAR**
16 October 2003

Certified copies of the corresponding Convention application(s) were submitted to the International Bureau in PCT Application No. PCT/JP04/15101. Receipt of the certified copy(s) by the International Bureau in a timely manner under PCT Rule 17.1(a) has been acknowledged as evidenced by the attached PCT/IB/304.

Respectfully submitted,
OBLON, SPIVAK, McCLELLAND,
MAIER & NEUSTADT, P.C.



Norman F. Oblon
Attorney of Record
Registration No. 24,618
Surinder Sachar
Registration No. 34,423

Customer Number

22850

(703) 413-3000
Fax No. (703) 413-2220
(OSMMN 08/03)